

Asok K Barua

List of Publications by Year in Descending Order

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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

141
papers

1,556
citations

19
h-index

32
g-index

148
ext. papers

1,674
ext. citations

2.7
avg, IF

3.77
L-index

#	Paper	IF	Citations
141	Properties of boron doped ZnO films prepared by reactive sputtering method: Application to amorphous silicon thin film solar cells. <i>Journal of Materials Science and Technology</i> , 2020 , 55, 136-143	9.1	7
140	Mixed-Phase nc-SiO _x :H Interlayer to Improve Light Trapping and Shunt Quenching in a-Si:H Solar Cell. <i>IEEE Journal of Photovoltaics</i> , 2019 , 9, 18-25	3.7	0
139	Innovative Utilization of Improved n-doped μ -SiO _x :H Films to Amplify the Performance of Micromorph Solar Cells. <i>Silicon</i> , 2019 , 11, 487-493	2.4	3
138	Sacrificial layer assisted front textured glass substrate with improved light management in thin film silicon solar cells. <i>Journal of Materials Science: Materials in Electronics</i> , 2019 , 30, 2622-2629	2.1	1
137	Texturization of ZnO:Al surface by reactive ion etching in SF ₆ /Ar, CHF ₃ /Ar plasma for application in thin film silicon solar cells. <i>Journal of Materials Science: Materials in Electronics</i> , 2018 , 29, 6206-6214	2.1	4
136	Parasitic loss mitigation and photocurrent enhancement in amorphous silicon solar cells by using phosphorous-doped fluorinated μ c-SiO:H back reflector. <i>Journal of Materials Science: Materials in Electronics</i> , 2018 , 29, 11104-11116	2.1	2
135	Reduction of Hole Injection Barrier Height at TCO/P Interface Using a-SiO:H Interlayer. <i>IEEE Journal of Photovoltaics</i> , 2018 , 8, 8-15	3.7	3
134	Optimization of the texturization of ZnO:Al surface using HCl + HNO ₃ for application in thin film silicon solar cells. <i>Journal of Materials Science: Materials in Electronics</i> , 2018 , 29, 3210-3218	2.1	4
133	Band Offset Reduction at Defect-Rich p/i Interface Through a Wide Bandgap a-SiO:H Buffer Layer. <i>IEEE Journal of Photovoltaics</i> , 2017 , 7, 414-420	3.7	12
132	Development of Improved n- μ -SiO _x :H Films and Its Innovative Application in Silicon-Based Single Junction Thin Film Solar Cells. <i>IEEE Journal of Photovoltaics</i> , 2017 , 7, 892-899	3.7	4
131	Role of dual SiO _x :H based buffer at the p/i interface on the performance of single junction microcrystalline solar cells. <i>Materials Science in Semiconductor Processing</i> , 2017 , 66, 9-14	4.3	1
130	Influence of excitation frequency and electrode separation on the growth of microcrystalline silicon films and their application in single junction microcrystalline solar cell. <i>Journal of Materials Science: Materials in Electronics</i> , 2017 , 28, 10382-10390	2.1	2
129	Development of n-type microcrystalline SiO _x :H films and its application by innovative way to improve the performance of single junction μ c-Si:H solar cell. <i>Journal of Materials Science: Materials in Electronics</i> , 2017 , 28, 5746-5753	2.1	4
128	Blue and violet defect levels mediated absorption hot spots in tapered ZnO nanorods toward improved photocatalytic activity. <i>Journal of Materials Science</i> , 2017 , 52, 12818-12825	4.3	1
127	Effect of oxide based graded buffer and bottom n-layer on the performance of the single junction amorphous silicon solar cells. <i>Journal of Materials Science: Materials in Electronics</i> , 2017 , 28, 16165-16172	2.1	1
126	Numerical modelling on stress and dislocation generation in multi-crystalline silicon during directional solidification for PV applications. <i>Electronic Materials Letters</i> , 2016 , 12, 431-438	2.9	16
125	Hierarchical indium tin oxide (ITO) nano-whiskers: Electron beam deposition and sub-bandgap defect levels mediated visible light driven enhanced photocatalytic activity. <i>Catalysis Communications</i> , 2016 , 87, 86-89	3.2	7

124	Fabrication of single junction amorphous silicon solar cell/mini module using novel n-type nanocrystalline SiOx:F:H back reflector. <i>Journal of Materials Science: Materials in Electronics</i> , 2015 , 26, 331-335	2.1	3
123	Silicon heterojunction solar cells with novel fluorinated n-type nanocrystalline silicon oxide emitters on p-type crystalline silicon. <i>Japanese Journal of Applied Physics</i> , 2015 , 54, 08KD03	1.4	2
122	The influence of hydrogen gas in the ambient gas mixture on the properties of indium tin oxide films deposited on glass and acrylic substrates by dc magnetron sputtering. <i>Journal Physics D: Applied Physics</i> , 2006 , 39, 3838-3843	3	4
121	Preparation and characterization of n-type microcrystalline hydrogenated silicon oxide films. <i>Journal Physics D: Applied Physics</i> , 2002 , 35, 1205-1209	3	24
120	Development of stabilized dual gap double junction a-Si solar cell using helium diluted a-Si : H intrinsic layer. <i>Journal Physics D: Applied Physics</i> , 2002 , 35, 3060-3064	3	2
119	Role of hydrogen in controlling the growth of μ -Si:H films from argon diluted SiH ₄ plasma. <i>Journal of Applied Physics</i> , 2002 , 91, 5442-5448	2.5	37
118	Development of High Quality P-Type Hydrogenated Amorphous Silicon Oxide Film and Its Use in Improving the Performance of Single Junction Amorphous Silicon Solar Cells. <i>Japanese Journal of Applied Physics</i> , 2002 , 41, 765-769	1.4	19
117	The Growth of Crystallinity in Undoped SiO:H Films at Low RF-Power Density and Substrate Temperature. <i>Japanese Journal of Applied Physics</i> , 2001 , 40, L94-L96	1.4	6
116	Heterogeneity in microcrystalline-transition state: Origin of Si-nucleation and microcrystallization at higher rf power from Ar-diluted SiH ₄ plasma. <i>Journal of Applied Physics</i> , 2001 , 89, 3041-3048	2.5	42
115	Control of Crystallization at Low Thickness in μ c-Si:H Films Using Layer-by-Layer Growth Scheme. <i>Japanese Journal of Applied Physics</i> , 1999 , 38, L1087-L1090	1.4	22
114	The role of ZnO:Al films in the performance of amorphous-silicon based tandem solar cells. <i>Journal Physics D: Applied Physics</i> , 1999 , 32, 213-218	3	24
113	Improvement in the optoelectronic properties of a-SiO:H films. <i>Journal of Materials Science</i> , 1999 , 34, 1051-1054	4.3	12
112	Intrinsic Hydrogenated Microcrystalline Silicon Oxide Films Prepared by RF Glow Discharge. <i>Journal of Materials Science Letters</i> , 1998 , 17, 2097-2100		9
111	Textured aluminium-doped ZnO thin films prepared by magnetron sputtering. <i>Journal Physics D: Applied Physics</i> , 1996 , 29, 1873-1877	3	18
110	Study of effects of interelectrode spacing and preheating of source gases on hydrogenated amorphous silicon films prepared at high growth rates. <i>Journal of Applied Physics</i> , 1995 , 78, 3193-3199	2.5	5
109	Efficient Boron Incorporation in Hydrogenated Amorphous Silicon Films by a Novel Combination of RF Glow Discharge Technique and Heated Filament. <i>Japanese Journal of Applied Physics</i> , 1995 , 34, 5743-5750	1.4	7
108	Role of boron in the structural and electronic properties of hydrogenated silicon films deposited by r.f. magnetron sputtering. <i>The Philosophical Magazine: Physics of Condensed Matter B, Statistical Mechanics, Electronic, Optical and Magnetic Properties</i> , 1995 , 71, 115-125		1
107	The role of hydrogen dilution and radio frequency power in the formation of microcrystallinity of n-type Si:H thin film. <i>Journal of Applied Physics</i> , 1993 , 74, 5561-5568	2.5	29

106	Diamond-Like Carbon Films Prepared by Photochemical Vapour Deposition. <i>Japanese Journal of Applied Physics</i> , 1993 , 32, L1559-L1561	1.4	10
105	Hydrogen plasma degradation of SnO ₂ :F films prepared by the APCVD method. <i>Journal Physics D: Applied Physics</i> , 1993 , 26, 2144-2147	3	7
104	Control of powder formation in silane discharge by cathode heating and hydrogen dilution for high-rate deposition of hydrogenated amorphous silicon thin films. <i>Journal of Applied Physics</i> , 1993 , 74, 4540-4545	2.5	10
103	Hydrogenated amorphous silicon films prepared at high substrate temperature: Properties and light induced degradation. <i>Journal of Applied Physics</i> , 1993 , 73, 7435-7440	2.5	7
102	Effect of hydrogen flow rate on the properties of magnetron sputtered hydrogenated microcrystalline silicon. <i>Journal of Materials Science Letters</i> , 1993 , 12, 1316-1319		2
101	Role of hydrogen dilution and diborane doping on the growth mechanism of p-type microcrystalline silicon films prepared by photochemical vapor deposition. <i>Journal of Applied Physics</i> , 1992 , 71, 5205-5211	2.5	32
100	Formation of microcrystallinity in hydrogenated silicon films deposited with a simple modification of the magnetron sputtering method. <i>Journal of Materials Science Letters</i> , 1991 , 10, 1468-1470		3
99	Study of hydrogenated amorphous silicon nitride films prepared by RF magnetron sputtering. <i>Applied Physics A: Solids and Surfaces</i> , 1991 , 52, 339-343		2
98	Laser-induced structural changes in magnetron-sputtered hydrogenated microcrystalline silicon films. <i>Physical Review B</i> , 1991 , 43, 4503-4506	3.3	7
97	Polycrystalline silicon carbide films deposited by low-power radio-frequency plasma decomposition of SiF ₄ -CF ₄ -H ₂ gas mixtures. <i>Journal of Applied Physics</i> , 1991 , 69, 3915-3923	2.5	25
96	Influence of Chamber Pressure on Hydrogen Bonding Configurations in a-SiGe:H Films Prepared by Photo-CVD. <i>Japanese Journal of Applied Physics</i> , 1990 , 29, 2365-2370	1.4	3
95	Radiofrequency-plasma-deposited hydrogenated fluorinated silicon-carbon alloy films. <i>Physical Review B</i> , 1989 , 40, 3830-3836	3.3	10
94	Comparison of the properties of hydrogenated microcrystalline silicon films deposited by photochemical-vapor deposition and glow-discharge deposition processes. <i>Journal of Applied Physics</i> , 1989 , 66, 4709-4714	2.5	11
93	Low-power deposition of fluorinated microcrystalline silicon hydrogen alloy films. <i>Journal of Applied Physics</i> , 1989 , 65, 4024-4027	2.5	8
92	Effect of ultraviolet irradiation on the white light degraded electronic properties of hydrogenated amorphous silicon films. <i>Applied Physics Letters</i> , 1989 , 55, 1975-1977	3.4	7
91	Phosphorus Doping and Photoinduced Changes in Hydrogenated Amorphous Silicon-Carbon Alloy Films. <i>Japanese Journal of Applied Physics</i> , 1989 , 28, 1776-1779	1.4	7
90	Microcrystalline Silicon Films Produced by RF Magnetron Sputtering and the Effect of Different Ambients on their Conductivity. <i>Materials Research Society Symposia Proceedings</i> , 1989 , 164, 69		1
89	A Simple Modification of the Magnetron Sputtering Method for Deposition of Hydrogenated Amorphous Silicon Films with Improved Optoelectronic Properties. <i>Japanese Journal of Applied Physics</i> , 1988 , 27, L1806-L1808	1.4	2

88	Degradation of tin-doped indium-oxide film in hydrogen and argon plasma. <i>Journal of Applied Physics</i> , 1987 , 62, 912-916	2.5	87
87	Influence of deposition parameters on the properties of boron-doped amorphous silicon-carbide films. <i>Journal of Applied Physics</i> , 1987 , 62, 3917-3921	2.5	9
86	Thickness dependence of the properties of magnetron sputtered indium tin oxide films. <i>Journal of Materials Science Letters</i> , 1987 , 6, 1203-1204		7
85	Photo-induced changes in the properties of undoped and boron-doped a-Si:H films. <i>The Philosophical Magazine: Physics of Condensed Matter B, Statistical Mechanics, Electronic, Optical and Magnetic Properties</i> , 1986 , 54, 301-309		19
84	Structural characterization of tin doped indium oxide films prepared by magnetron sputtering. <i>Journal of Materials Science</i> , 1985 , 20, 2937-2944	4.3	9
83	Photodissociation of HeH ⁺ molecular ion. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1984 , 17, 1537-1545		8
82	Properties of tin doped indium oxide thin films prepared by magnetron sputtering. <i>Journal of Applied Physics</i> , 1983 , 54, 3497-3501	2.5	266
81	Photodissociation of MgH in the solar atmosphere. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1983 , 16, 2377-2384		3
80	Properties of Tellurium Doped Vacuum Evaporated CdS Thin Films. <i>Japanese Journal of Applied Physics</i> , 1982 , 21, L43-L45	1.4	2
79	Transport properties of lithium and sodium doped nickel oxide. <i>Physica Status Solidi A</i> , 1981 , 65, 365-370		25
78	Rotational cross sections and rate coefficients fore-CO and HCN collisions under interstellar conditions. <i>Physical Review A</i> , 1981 , 23, 2926-2932	2.6	9
77	Properties of Vacuum-Evaporated CdS Thin Films. <i>Japanese Journal of Applied Physics</i> , 1980 , 19, 1889-1895	1.4	39
76	Photodissociation of H ₂ ⁺ by the 1s σ -np π transition. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1980 , 13, 3755-3762		8
75	The diffusion of nickel into copper and copper-nickel alloys. <i>Physica Status Solidi A</i> , 1979 , 56, 149-155		15
74	The effect of a magnetic field on the thermal conductivity of NO ₂ and NO ₂ mixtures. <i>Journal of Chemical Physics</i> , 1979 , 71, 1414-1417	3.9	1
73	Total Cross Sections of Na Scattered by Different Gases. <i>Journal of the Physical Society of Japan</i> , 1979 , 46, 205-207	1.5	
72	Photodissociation of HeH ₂ ⁺ and flux deficiency of stellar spectra. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1979 , 12, 3553-3561		5
71	The diffusion of iron in copper and of nickel in silver. <i>Physica Status Solidi A</i> , 1978 , 45, 657-663		23

70	Photodissociation of HeH ⁺ by both electronic and vibrational transitions. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1978 , 11, 3349-3356		13
69	Rotational transitions of HD ⁺ in collisions with He. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1978 , 11, 1953-1963		1
68	Small-angle scattering in atom-molecule collisions: an interpretation of experimental results for the Ar-TlF system. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1978 , 11, 1965-1973		1
67	The effect of magnetic field on the heat conductivity of O ₂ N ₂ and O ₂ H ₂ gas mixtures. <i>Journal of Chemical Physics</i> , 1978 , 68, 3226-3230	3.9	3
66	Rotational transitions in collisions between polar molecules: an application of the semiclassical strong-coupling method to HCl-HCl collisions. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1977 , 10, 1557-1572		7
65	Rotational transitions in collisions between molecular ions: First-order calculations for HD ⁺ -HD ⁺ . <i>Physical Review A</i> , 1977 , 16, 144-149	2.6	1
64	Molecular Beam Studies of Total Cross Sections of Na Scattered by Different Gases. <i>Journal of the Physical Society of Japan</i> , 1977 , 42, 616-620	1.5	2
63	The effect of nonspherical interactions on the collision integrals for HeH ₂ , HeHD, and HeHT systems. <i>Journal of Chemical Physics</i> , 1976 , 64, 5312-5313	3.9	1
62	Thermal diffusion in binary mixtures of linear molecules. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1976 , 9, 1975-1987		2
61	The effect of non-spherical potential terms on the interaction second virial coefficient for the systems He-H ₂ , He-HD and He-HT. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1976 , 9, 2723-2730		1
60	The electrical resistivity and temperature coefficient of resistivity of cobalt films. <i>Journal Physics D: Applied Physics</i> , 1976 , 9, 2261-2267	3	16
59	Semiclassical strong-coupling calculations for rotational excitation of HCN by collision with H ₂ . <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1976 , 9, 2341-2353		2
58	Impurity diffusion in metals. Tin in copper and lead in silver. <i>Physica Status Solidi A</i> , 1975 , 32, 345-350		13
57	Effects of agglomeration and magnetic boundary scattering on the electrical resistivity of nickel films. <i>Journal of Applied Physics</i> , 1975 , 46, 3465-3467	2.5	5
56	Dissociation of H ₂ ⁺ ion by collision-induced vibrational excitation. <i>Journal of Chemical Physics</i> , 1975 , 62, 4373-4379	3.9	11
55	Vibrational-rotational excitations of the (HeH) ⁺ ion by collisions with positrons. <i>Physical Review A</i> , 1975 , 12, 796-800	2.6	2
54	Rotational excitation of HD ⁺ by electron and positron impact. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1975 , 8, 2283-2292		5
53	Studies on the Thermal Diffusion in the Binary Gas Mixtures Ne-N ₂ O and Kr-N ₂ O. <i>Journal of the Physical Society of Japan</i> , 1974 , 37, 1089-1097	1.5	2

52	Thermal diffusion in polyatomic gas mixtures: methane-nitrogen and methane-carbon dioxide systems. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1974 , 7, 178-184		7
51	Semiclassical close-coupling calculations for rotational transitions in polar diatom-atom collisions. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1974 , 7, 2264-2276		12
50	Dissociation of the (HeH) ⁺ molecular ion using elliptic-type orbitals. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1974 , 7, 288-296		3
49	Effect of short range interactions on rotational transitions of CO and NO molecules by low energy electron collisions. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1974 , 7, 973-979		3
48	Rainbow structure for the Kihara core potential by using the uniform approximation. <i>Zeitschrift für Physik A</i> , 1973 , 261, 273-282		
47	On the dielectric second virial coefficient of polar gases. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1973 , 6, 1327-1332		3
46	Rotational inelasticity in polar diatom-atom scattering: application of the semi-classical time-dependent perturbation theory to the Ne-CO and Ne-HCl systems. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1973 , 6, 1824-1835		7
45	Viscosity of the binary gas mixtures argon-methane and argon-ammonia. <i>Journal of Chemical Physics</i> , 1973 , 59, 3633-3638	3.9	13
44	Thermal Diffusion in Non-Polar-Polar System: Ne-CH ₃ Cl and Ar-CH ₃ Cl. <i>Journal of the Physical Society of Japan</i> , 1973 , 34, 1351-1355	1.5	3
43	Contributions of nonspherical and nonadditive molecular interactions to the third virial coefficient of a diatomic and polyatomic gas. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1972 , 5, 1676-1680		1
42	Distortion polarization of orbitals and the asymmetry in the forward-backward scattering fragments from dissociation of (HeH) ⁺ ion. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1972 , 5, 1381-1385		2
41	Contributions of the non-spherical interactions to the third virial coefficient of a polyatomic gas. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1972 , 5, 16-26		2
40	Transport properties and second virial coefficient of nonpolar-polar gas mixtures. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1972 , 5, 1950-1958		2
39	Effect of dipole moment on the collision induced dissociation of HD ⁺ ion by electron impact. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1972 , 5, 1369-1380		4
38	On the Inversion from the Energy Dependence of Total Cross-Sections. <i>Journal of the Physical Society of Japan</i> , 1972 , 33, 468-472	1.5	
37	Total Cross-Sections for Dipole-Dipole Scattering by Using Effectively Spherically Symmetric Potentials. <i>Journal of the Physical Society of Japan</i> , 1971 , 30, 1158-1165	1.5	2
36	Thermal Diffusion in the System Argon-Methane. <i>Journal of the Physical Society of Japan</i> , 1971 , 31, 250-254		5
35	Angular Distribution of H ⁺ or D ⁺ from the Electron Impact Dissociation of HD ⁺ Ion. <i>Journal of the Physical Society of Japan</i> , 1971 , 31, 230-235	1.5	3

34	Heat conductivity of the nonpolar-polar gas mixtures Ar-CH ₃ Cl and Xe-CH ₃ Cl. <i>Journal of Physics A: General Physics</i> , 1971 , 4, 944-951		1
33	On the asymmetry in the angular distribution of the fragments produced from the collision induced dissociation of HD ⁺ ion. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1971 , 4, 1450-1457		7
32	Thermal diffusion in polyatomic gas mixtures : methane+methyl chloride system. <i>Transactions of the Faraday Society</i> , 1970 , 66, 1604		8
31	Dipole-dipole interaction and viscosity of polar gases. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1970 , 3, 526-535		14
30	Thermal diffusion in polyatomic gas mixtures. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1970 , 3, 1052-1061		3
29	Relaxation effects and the thermal conductivity of polyatomic gases and gas mixtures. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1970 , 3, 619-635		5
28	Composition dependence of the thermal diffusion factor for the system CO-CH ₃ Cl and CO ₂ -CH ₃ Cl. <i>Journal of Physics B: Atomic and Molecular Physics</i> , 1969 , 2, 715-718		2
27	Thermal Diffusion in the Nonpolar-Polar System Helium-Methyl Chloride. <i>Journal of Chemical Physics</i> , 1969 , 50, 2052-2056	3.9	4
26	Thermal Diffusion in Argon-Carbon Dioxide Gas Mixture. <i>Journal of Chemical Physics</i> , 1968 , 48, 5238-5241	3.9	14
25	Composition Dependence of the Thermal-Diffusion Factor in the Hydrogen-Helium Gas Mixture. <i>Journal of Chemical Physics</i> , 1968 , 48, 2802-2805	3.9	12
24	Thermal Conductivity and Rotational Relaxation in Some Polar Gases. <i>Journal of Chemical Physics</i> , 1968 , 49, 2422-2425	3.9	14
23	Thermal diffusion in the ternary system helium + neon + carbon dioxide. <i>Transactions of the Faraday Society</i> , 1968 , 64, 358		3
22	Intermolecular potentials and viscosities of some polar organic vapours. <i>Journal Physics D: Applied Physics</i> , 1968 , 1, 71-76	3	5
21	Effect of chemical reaction on diffusion in the system N ₂ O ₄ ⇌ 2NO ₂ . <i>Journal of Physics A</i> , 1968 , 1, 269-271		
20	Thermal Conductivity of Argon-Carbon dioxide and Nitrogen-Carbon dioxide Gas Mixtures. <i>Journal of the Physical Society of Japan</i> , 1968 , 25, 862-867	1.5	11
19	On the representation of the interaction energy between two polar molecules. <i>Flow, Turbulence and Combustion</i> , 1968 , 18, 43-49		2
18	Formation of Dimers in Polar Gases: Contribution of Metastably Bound Molecules to the Second Virial Coefficient. <i>Journal of the Physical Society of Japan</i> , 1967 , 22, 77-81	1.5	4
17	Thermal conductivities of nitrogen-argon and oxygen-argon gas mixtures. <i>British Journal of Applied Physics</i> , 1967 , 18, 1307-1310		14

16	Heat conductivity and relaxation effects in the system $\text{N}_2\text{O}_4 \rightleftharpoons 2\text{NO}_2$. <i>Proceedings of the Physical Society</i> , 1967 , 92, 800-804		2
15	Thermal conductivity of some quadrupolar gases. <i>Transactions of the Faraday Society</i> , 1967 , 63, 2379		13
14	Thermal Diffusion in Hydrogen-Helium Gas Mixture. <i>Journal of Chemical Physics</i> , 1967 , 47, 452-453	3.9	15
13	Improved Design for the Trennschaukel: Measurement of the Thermal-Diffusion Factors in Gas Mixtures. <i>Journal of Chemical Physics</i> , 1967 , 47, 448-451	3.9	11
12	Thermal conductivity of hydrogen-nitrogen and hydrogen-carbon-dioxide gas mixtures. <i>British Journal of Applied Physics</i> , 1967 , 18, 1301-1306		13
11	Viscosity and intermolecular potentials of hydrogen sulphide, sulphur dioxide and ammonia. <i>Transactions of the Faraday Society</i> , 1967 , 63, 341		28
10	Thermal conductivity of hydrogen-helium gas mixtures. <i>British Journal of Applied Physics</i> , 1967 , 18, 635-640		31
9	Chemical reaction and diffusion coefficients in the heat conductivity of chemically reacting gas mixtures. <i>Transactions of the Faraday Society</i> , 1966 , 62, 3131		3
8	The influence of bound molecules on the thermal conductivity in the critical region. <i>Flow, Turbulence and Combustion</i> , 1965 , 15, 313-321		1
7	Force Constants of N_2O_4 and NO_2 and the Viscosity of the Dissociating System $\text{N}_2\text{O}_4 \rightleftharpoons 2\text{NO}_2$. <i>Journal of Chemical Physics</i> , 1965 , 43, 4140-4142	3.9	9
6	Viscosity of Hydrogen, Deuterium, Methane, and Carbon Monoxide from 80°K to 150°C below 200 Atmospheres. <i>Journal of Chemical Physics</i> , 1964 , 41, 374-378	3.9	56
5	Thermal conductivity of slowly reacting systems. <i>Transactions of the Faraday Society</i> , 1963 , 59, 2522		3
4	Thermal Conductivity and Equilibrium Constant of the System $\text{N}_2\text{O}_4 \rightleftharpoons 2\text{NO}_2$. <i>Journal of Chemical Physics</i> , 1961 , 35, 329-334	3.9	20
3	Effect of Relaxation of Chemical Energy on the Thermal Conductivity of the System $\text{N}_2\text{O}_4 \rightleftharpoons 2\text{NO}_2$. <i>Journal of Chemical Physics</i> , 1961 , 35, 649-651	3.9	3
2	Rotational-Translational Relaxation Time in H_2 Calculated from Thermal Conductivity. <i>Proceedings of the Physical Society</i> , 1961 , 77, 677-681		2
1	Thermal Conductivity of Binary Mixtures of Diatomic and Monatomic Gases. <i>Journal of Chemical Physics</i> , 1960 , 32, 427-435	3.9	35